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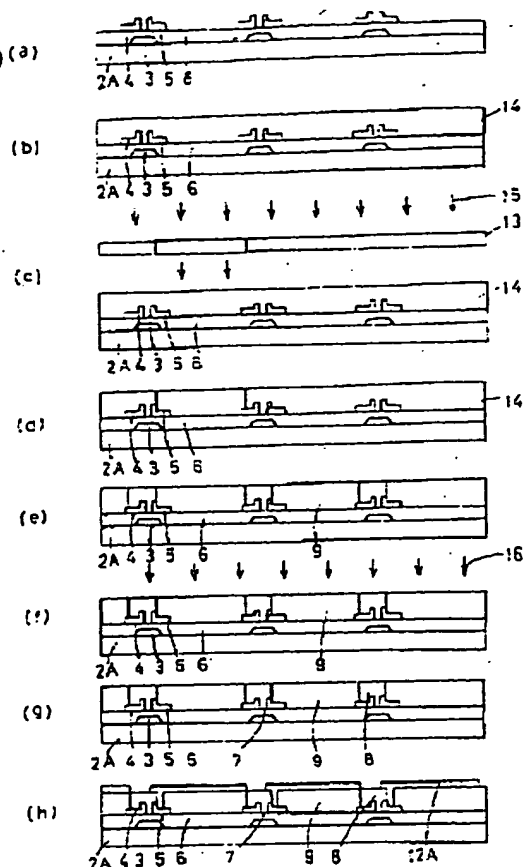
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TITLE : ACTIVE MATRIX SUBSTRATE AND
MANUFACTURE THEREOF

B88 (a)



ABSTRACT : PROBLEM TO BE SOLVED: To provide an active matrix substrate, which is provided with a high yield, high brightness, and a high contrast, and a manufacturing method thereof.

SOLUTION: After a nonlinear element constructed of a thin film transistor is formed, an organic polymer insulating film 14 made of organic polysilane and the like is applied once, and then, a contact hole reaching a drain electrode in the thin film transistor is bored in the organic polymer insulating film 14, and subsequently, a part of the organic polymer insulating film 14 is colored in three colors R, G, B while the rest part is colored in black, and consequently, a color filter 9 and a black matrix 8 are formed in the organic polymer insulating film 14. An ITO pixel electrode 12A is formed on the color filter 9 so as to be connected to the drain electrode in the thin film transistor through the contact hole.

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